



PATENT APPLICATION

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FONES

Entered
5-27-03
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Yasunaga KAYAMA

Group Art Unit: 2851

Application No.: 09/713,215

Examiner: P. Kim

Filed: November 16, 2000

Docket No.: 107314

For: EXPOSURE APPARATUS AND METHOD THAT EXPOSES A PATTERN ONTO A
SUBSTRATE (AS AMENDED)

AMENDMENT FILED WITH RCE

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Upon entry of the Request for Continued Examination (RCE) filed herewith, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1, 18 and 30 as follows:

1. (Twice Amended) An exposure apparatus that exposes a pattern onto a substrate, the exposure apparatus comprising:

a projection system to project the pattern onto the substrate;

a holder connected to the projection system to hold the projection system;

a main frame that mounts the projection system by means of the holder;

a detector to detect information concerning displacement of the projection

system;

an actuator arranged on the holder; and

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